

EAST

7/29/05

1 of 3

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	11019	((aperture or hole or opening or step or illumination or illuminance) near2 angle).clm.	US-PGPUB; USPAT; DERWENT	OR	ON	2005/07/29 11:16
L3	212613	first near2 (division or subdivision or section or subsection or area or subarea or region or subregion or pitch).clm.	US-PGPUB; USPAT; DERWENT	OR	ON	2005/07/29 11:17
L4	192009	second near2 (division or subdivision or section or subsection or area or subarea or region or subregion or pitch).clm.	US-PGPUB; USPAT; DERWENT	OR	ON	2005/07/29 11:18
L5	7171	((full or total or complete or "100") near3 (light or radiation or beam) or non adj shadow or 'all light' or 'all radiation').clm.	US-PGPUB; USPAT; DERWENT	OR	ON	2005/07/29 11:17
L6	73386	((part or partial mixed or portion) near3 (light or radiation or beam) or shadow).clm.	US-PGPUB; USPAT; DERWENT	OR	ON	2005/07/29 11:18
L7	36561	(calculat\$3 or determin\$3 or measur\$4 or sens\$3 or detect\$3) near5 (intensity or density or contrast).clm.	US-PGPUB; USPAT; DERWENT	OR	ON	2005/07/29 11:19
L8	71414	(divid\$3 or subdivid\$3 or section\$3 or subsection\$3 or subregion or region or area or subarea) near4 (substrate or wafer).clm.	US-PGPUB; USPAT; DERWENT	OR	ON	2005/07/29 11:19
L9	0	8 and (3 same 5) and (4 same 6) and (3 same 7) and (4 same 7)	US-PGPUB; USPAT; DERWENT	OR	ON	2005/07/29 11:00
L10	1	8 and (3 same 5) and (4 same 6) and 2	US-PGPUB; USPAT; DERWENT	OR	ON	2005/07/29 11:09
L11	6	simulat\$3 near4 (lithography or microlithography or photolithography).clm. and 8	US-PGPUB; USPAT; DERWENT	OR	ON	2005/07/29 11:07
L12	5027	(calculat\$3 or design\$3 or determin\$3) same (reticle or mask or pattern) same (intensit\$3 or radiation or light or pitch or contrast).clm.	US-PGPUB; USPAT; DERWENT	OR	ON	2005/07/29 11:09
L13	0	8 and (3 same 5) and (4 same 6) and 12	US-PGPUB; USPAT; DERWENT	OR	ON	2005/07/29 11:10
L14	0	(correct\$3 or modify\$3 or chang\$3 or adjust\$5 or modification) same (shape or mask or reticle or pattern).clm. and 8 and (3 same 5) and (4 same 6)	US-PGPUB; USPAT; DERWENT	OR	ON	2005/07/29 11:15

L15	68838	((aperture or hole or opening or step or illumination or illuminance) near2 angle)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/29 11:16
L16	212613	first near2 (division or subdivision or section or subsection or area or subarea or region or subregion or pitch).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/29 11:17
L17	105292	((full or total or complete or "100") near3 (light or radiation or beam) or non adj shadow or 'all light' or 'all radiation')	US-PGPUB; USPAT; DERWENT	OR	ON	2005/07/29 11:17
L18	452973	second near2 (division or subdivision or section or subsection or area or subarea or region or subregion or pitch)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/29 11:18
L19	453703	((part or partial mixed or portion) near3 (light or radiation or beam) or shadow)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/29 11:18
L20	333569	(calculat\$3 or determin\$3 or measur\$4 or sens\$3 or detect\$3) near5 (intensity or density or contrast)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/29 11:19
L21	346568	(divid\$3 or subdivid\$3 or section\$3 or subsection\$3 or subregion or region or area or subarea) near4 (substrate or wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/29 11:20
L22	30221	(355/53,67-69,77.ccls. or 250/492.1,492.2,548.ccls. or 430/5,30,311,322.ccls. or 716/19-21.ccls. or 382/144-150.ccls. or 703/2.ccls.)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/29 11:25
L23	0	22 and 2 and (16 same 17) and (18 same 19) and 21	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/29 11:26
L24	1	22 and (16 same 17) and (18 same 19) and 21	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/29 11:27
L25	0	22 and (16 same 17) and (18 same 19) and (20 same 16) and (20 same 18)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/29 11:27